Serial No. 10/040017

1752

#6

IN THE UNITED STATES
PATENT AND TRADEMARK OFFICE

PATENT APPLICATION

Inventor(s):   **Misha Megens**
                  Pierre Wiltzius
                  Shu Yang

Case: **1-10-5**

Serial No.:   **10/040017**

Filing Date: **January 4, 2002**

Examiner: Group Art Unit: **1752**

Title: **Fabricating Artificial Crystalline Structures**

ASSISTANT COMMISSIONER FOR PATENTS
  WASHINGTON, D. C. 20231

SIR:

INFORMATION DISCLOSURE STATEMENT
UNDER 37 CFR 1.97(b)

In accordance with 37 CFR 1.97(b), the enclosed Information Disclosure Statement, with attached reference(s), is submitted for consideration in the above-identified application.

Copies of the listed documents are enclosed.

NO FEE IS REQUIRED

In the event of any non-payment or improper payment of a required fee, the Commissioner is authorized to charge or to credit **Lucent Technologies Deposit Account No. 12-2325** as required to correct the error.
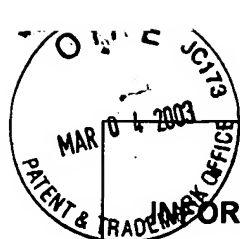
Respectfully,

John F. McCabe, Attorney
Reg. No. **42854**
908-582-6866

Date: 2/26/2003

Docket Administrator (Room 3J-219)
Lucent Technologies Inc.
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INFORMATION DISCLOSURE STATEMENT	Case Name.	M. Megens 1-10-5			
	Serial No.	10/040017			
	Applicant:	M. Megens, et al.			
	Filing Date:	January 4, 2002			
	Group:	1752			

(Stamps: PATENT & TRADEMARK OFFICE, MAR 04 2003; RECEIVED MAR 0 7 2003 GROUP 1700)

U.S. PATENT DOCUMENTS

*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Dat
	AA	5,248,734	9/28/93	Ober et al.	525	328.8	6/16/92
	AB	5,665,527	9/9/97	Allen et al.	430	325	2/3/97
	AC	6,329,070 B1	12/11/01	Sass et al.	428	612	12/7/00
	AD	6,379,874 B1	4/30/02	Ober et al.	430	322	10/16/00
	AE	Serial No. 10/321027		Reichmanis et al.			12/17/02
	AF	5,922,299	7/13/99	Bruinsma et al.	423	335	8/26/97
	AG	Serial No. 10/098286		C.H. Chen et al.			3/15/02

FOREIGN PATENT DOCUMENTS

		Document Number	Date	Country	Class	Subclass	Translation
	AH	WO 01/42540 A1	6/14/01	PCT	C30B	33/00	Yes
	AI	WO 01/51990 A1	7/19/01	PCT	G03C	5/00	Yes
	AJ	WO 01/31404 A1	5/3/01	PCT	G03F	7/30	Yes

OTHER (including Author, Title, Date, Pertinent Pages, etc.)

	AK	Sundararajan, N., et al., "Supercritical CO_2 Processing for Submicron Imaging of Fluoropolymers," *Chemistry of Materials*, Vol. 12, No. 1, January 2000, pps. 41-48.
	AL	Kresge, C.T., et al: "Ordered mesoporous molecular sieves synthesized by a liquid-crystal template mechanism" NATURE, vol. 359, October, 1992, pp. 710-712.
	AM	Tanev, Peter T., et al: "A Neutral Templating Route to Mesaporous Molecular Sieves," SCIENCE, vol. 267, February, 1995, pp. 865-867.
	AN	Huo, Q. et al: "Generalized synthesis of periodic surfactant/inorganic composite materials," NATURE, vol. 368, March, 1994, pp. 317-321.
	AO	Sanchez, C., et al: "Design and Properties of Hybrid Organic-Inorganic Nanocomposites for Photonics," MRS Bulletin, May, 2001, pp. 377-387.
	AP	Yang, P., et al: "Hierarchically Ordered Oxides," Science, vol. 282, December 1998, pp. 2244-2246.
	AQ	Templin, M. et al: "Organically Modified Aluminosilicate Mesostructures from Block Copolymer Phases," Science, vol. 278, December, 1997, pp. 1795-1798.
	AR	Raman, N.K., et al: "Template-Based Approaches to the Preparation of Amorphous, Nanoporous Silicas," Chemical Matter, vol. 8, February, 1996, pp. 1682-1701.
	AS	Yang, P., et al: "Block Copolymer Templating Syntheses of Mesoporous Metal Oxides with Large Ordreing Lengths and Semicrystalline Framework," Chemical Matter, vol. 11, 1999, pp. 2813-2826.
	AT	Brinker, C.J., et al., "Evaporation-Induced Self-Assembly: Nanostructures Made Easy**" Advanced Materials, vol. 11, 1999, pp. 579-585.

***References listed beyond AZ would list as AA-1, AB-2, AC-3 thru AZ-26.*
***Note First Page ONLY Header/Footer. Subsequent pages must ONLY have <u>page # layout</u> as header*

EXAMINER	DATE CONSIDERED

*Examin r: Initial if reference considered, whether or not citation is in conformance with MPEP 609: Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant